L Number	Hits	Search Text	DB	Time stamp
1	1	"20030008505"	US-PGPUB	2003/08/20 17:26
2	2	(silicide same (self near2 grow\$3)) same silicon	USPAT;	2003/08/20 17:57
			US-PGPUB;	
	:		EPO; JPO;	
			DERWENT;	
1			IBM_TDB	
3	1093	(silicide same grow\$3) same (silicon same etch\$3)	USPAT;	2003/08/20 17:32
	1000	(Sinciae dame grower) same (Sincer dame etemps)	US-PGPUB;	2000/00/20 17.02
			EPO; JPO;	
			DERWENT;	
			IBM_ TDB	
4	0	((silicide same grow\$3) same (silicon same etch\$3)) same	USPAT;	2003/08/20 17:32
7	U	(sincute same growps) same (sincorr same etchps)) same	US-PGPUB;	2003/00/20 17.32
		(nano near wire)	EPO; JPO;	
			DERWENT:	
			IBM_TDB	
5	0	(silicide same grow\$3) same (nano near wire)	USPAT;	2003/08/20 17:32
3	U	(Silicide Same grow\$5) Same (namo near wire)	US-PGPUB;	2003/06/20 17.32
			EPO; JPO;	
			DERWENT;	
	4.4		IBM_TDB	2002/00/00 47-22
6	14	grow\$3 same (nano near wire)	USPAT;	2003/08/20 17:32
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
-	5000	-10-14	IBM_TDB	00000000000000
7	5920	silicide same silicon	USPAT;	2003/08/20 17:57
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
	06	(alliaida aanaa alliaan) aanaa ((aniaataania@tanaanatab@Q) aanaa	IBM_TDB	0000/00/00 00 00
8	96	(silicide same silicon) same ((anisotropic\$4 near etch\$3) same	USPAT;	2003/08/20 20:00
		silicon)	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
10	0	(((silicide same silicon) same ((anisotropic\$4 near etch\$3)	IBM_TDB USPAT;	2003/08/20 18:00
'0	0	same silicon)) and @pd<20011113) and (nano near wire)	US-PGPUB;	2003/00/20 10.00
		same sincomy and wpu-20011113) and (nano near wire)	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
9	77	((silicide same silicon) same ((anisotropic\$4 near etch\$3)	USPAT;	2003/08/20 18:00
	′′	same silicon)) and @pd<20011113	US-PGPUB;	2003/00/20 10:00
		same silicon), and wpu-20011113	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
11	17532	(anisotropic\$4 near etch\$3) same silicon	USPAT;	2003/08/20 18:03
1	17002	Carrioda opiowa noar otonwo, sarite silloon	US-PGPUB;	2003/00/20 10:03
			EPO; JPO;	
	1		DERWENT;	
			IBM_TDB	
12	59	((anisotropic\$4 near etch\$3) same silicon) same (mask\$3	USPAT;	2003/08/20 18:03
'-	59	near5 silicide)	US-PGPUB;	2003/00/20 10:03
		noaro sinolao)	EPO; JPO;	
			DERWENT:	
			IBM TDB	
13	42	(((anisotropic\$4 near etch\$3) same silicon) same (mask\$3	USPAT;	2003/08/20 18:43
.	72	near5 silicide)) and @pd<20011113	US-PGPUB;	2000/00/20 10.43
		3	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
14	14	(nano near wire) same silicon	USPAT;	2003/08/20 19:38
'	, - 	(Hour tillo) dallid dilloon	US-PGPUB;	2000/00/20 13.30
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
L			I TOD	L

15	0	(nano near wire or nano near structure or nano near pattern) same ((epitaxial\$2 near grow\$3) same silicon)	USPAT; US-PGPUB;	2003/08/20 19:41
			EPO; JPO;	
			DERWENT;	
16	1	(nano near wire or nano near structure or nano near pattern)	IBM_TDB USPAT;	2003/08/20 19:45
10	•	same (epitaxial\$2 near grow\$3)	US-PGPUB;	2005/00/20 15.45
			EPO; JPO;	
			DERWENT;	
17	154063	(chab fig. on mothers fig.) come allinos	IBM_TDB	2002/00/20 40:45
17	154062	(etch\$3 or pattern\$3) same silicon	USPAT; US-PGPUB;	2003/08/20 19:45
1			EPO; JPO;	
			DERWENT;	
10	1510	(,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,	IBM_TDB	
18	1548	((etch\$3 or pattern\$3) same silicon) same (mask\$3 with	USPAT;	2003/08/20 19:46
		silicide)	US-PGPUB; EPO; JPO;	
			DERWENT;	
			IBM_TDB	
19	0	(((etch\$3 or pattern\$3) same silicon) same (mask\$3 with	USPAT;	2003/08/20 19:47
		silicide)) same nano	US-PGPUB;	
			EPO; JPO; DERWENT;	
			IBM TDB	
20	1213	(((etch\$3 or pattern\$3) same silicon) same (mask\$3 with	USPAT;	2003/08/20 19:54
		silicide)) and ((nano near wire) or (nano structure))	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
21	936	((((etch\$3 or pattern\$3) same silicon) same (mask\$3 with	USPAT;	2003/08/20 19:48
		silicide)) and ((nano near wire) or (nano structure))) and	US-PGPUB;	,
		insulat\$3	EPO; JPO;	
			DERWENT;	
22	0	(((((etch\$3 or pattern\$3) same silicon) same (mask\$3 with	USPAT;	2003/08/20 19:50
		silicide)) and ((nano near wire) or (nano structure))) and	US-PGPUB;	
		insulat\$3) and @pd<2001626	EPO; JPO;	
			DERWENT;	
23	532	(((((etch\$3 or pattern\$3) same silicon) same (mask\$3 with	IBM_TDB USPAT;	2003/08/20 19:54
20	552	silicide)) and ((nano near wire) or (nano structure))) and	US-PGPUB;	2000/00/20 10:04
		insulat\$3) and @pd<20010626	EPO; JPO;	
			DERWENT;	
24	1	((((((etch\$3 or pattern\$3) same silicon) same (mask\$3 with	IBM_TDB USPAT;	2003/08/20 19:52
		silicide)) and ((nano near wire) or (nano structure))) and	US-PGPUB;	2000/00/20 19.02
		insulat\$3) and @pd<20010626) and 216/41.ccls.	EPO; JPO;	
			DERWENT;	
25	0	(((etch\$3 or pattern\$3) same silicon) same (mask\$3 with	IBM_TDB USPAT;	2003/08/20 19:56
23		silicide)) and ((nano near wire) or (nano near structure))	US-PGPUB;	2003/06/20 18:30
			EPO; JPO;	
			DERWENT;	
26	0	(((atch\$3 or nattern\$3) same cilican) same (mask\$3 with	IBM_TDB USPAT;	2003/09/20 10:56
20		(((etch\$3 or pattern\$3) same silicon) same (mask\$3 with silicide)) and ((nano near wire) or (nano near structure))	US-PGPUB;	2003/08/20 19:56
1		(in the state of	EPO; JPO;	
			DERWENT,	
27	45	(/ailiaida agma ailiaan) agma (/anisatania@4 naga atat @2)	IBM_TDB	2002/09/20 20/22
27	45	((silicide same silicon) same ((anisotropic\$4 near etch\$3) same silicon)) and (insulat\$3)	USPAT; US-PGPUB;	2003/08/20 20:00
		Same smoothly and (modicities)	EPO; JPO;	
			DERWENT;	
L			IBM_TDB	